	Application No.	Applicant(s)		
Notice of Allowability	10/612,859	HUANG ET AL.		
	Examiner	Art Unit		
	Thao P. Le	2818		
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED or other appropriate completers. This application is	in this application. If not included nunication will be mailed in due cours		
1. This communication is responsive to <u>1/27/05</u> .				
2. The allowed claim(s) is/are 1-4 and 6-26.				
3. The drawings filed on 03 July 2003 are accepted by the Ex	aminer.			
 4. Acknowledgment is made of a claim for foreign priority una) All b) Some* c) None of the: Certified copies of the priority documents have Certified copies of the priority documents have Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 	been received. been received in Applica cuments have been received	tion No ed in this national stage application fr		
5. A SUBSTITUTE OATH OR DECLARATION must be subminformal PATENT APPLICATION (PTO-152) which give			E OF	
6. \square CORRECTED DRAWINGS (as "replacement sheets") must				
(a) including changes required by the Notice of Draftspers		ew (PTO-948) attached		
 1) ☐ hereto or 2) ☐ to Paper No./Mail Date (b) ☐ including changes required by the attached Examiner' 		or in the Office action of		
Paper No./Mail Date	04/-)) - tld bi44	About and in the forms (not the book	\ _	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	he header according to 37	CFR 1.121(d).) OI	
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT	sit of BIOLOGICAL MA FOR THE DEPOSIT OF E	TERIAL must be submitted. Note t HOLOGICAL MATERIAL.	he	
Attachment(s) 1. ⊠ Notice of References Cited (PTO-892)	5 Notice of	Informal Patent Application (PTO-152	1	
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)		Summary (PTO-413),	•/	
3. X Information Disclosure Statements (PTO-1449 or PTO/SB/0	Paper N	Paper No./Mail Date 7. ⊠ Examiner's Amendment/Comment		
Paper No./Mail Date 4.		8. ☑ Examiner's Statement of Reasons for Allowance 9. ☐ Other		

DETAILED ACTION

Response to Amendment

1. This Office Action is in response to Amendment filed on 01/27/05.

Claim 5 has been cancelled.

Claims 1 and 14 have been amended.

Claims 25-26 are newly added.

Claims 1-4, 6-26 are pending in the present application at the time of examination.

Remark of Applicants has been considered.

Examiner Amendment.

2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Amend claim 6 because claim 6 depends on a cancelled claim (claim 5) as follow:

Replace "The method of forming shallow trench isolation with chamfered corners of claim 5" with ---- The method of forming shallow trench isolation with chamfered corners of claim 1----.

Application/Control Number: 10/612,859 Page 3

Art Unit: 2818

Reason for allowance

3. Claims 1-4, 6-26 are allowed. The following is an examiner's statement of reason for allowance: None of the references of record teaches or suggests the claimed limitations having a method of forming a shallow trench isolation with chamfered corners comprising, among other steps cited in independent claims 1 and 14, the steps of pulling back the second mask layer a predetermined distance by wet etching to expose the first mask layer adjacent to the trench and result in the second mask layer having a tapered profile, and etching the second mask layer, the first mask layer, the pad insulating layer, and the substrate along the tapered profile of the second mask layer by anisotropic etching to chamfer corners of the trench.

4. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

Conclusion

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thao P. Le whose telephone number is 571-272-1785. The examiner can normally be reached on M-T (7-6).

Art Unit: 2818

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on 571-272-1787. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thao P. Le Examiner

Art Unit 2818